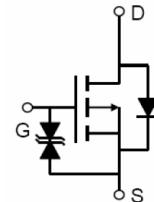


Trench P-Channel PowerMOSFET Wafer Datasheet

FEATURES

- -150V、40A*, P-channel
- $R_{DS(on)}=70\text{m}\Omega(\text{MAX})$
- Ultra low Q_{gd}
- Fast switching



Schematic diagram

Electrical Characteristics($T_J=25^\circ\text{C}$)

Parameter	Description	Min.	Typ.	Max.	Unit	Test Condition
$V_{(\text{BR})\text{DSS}}$	Drain-Source Breakdown Voltage	-150			V	$\text{VGS}=0\text{V}, \text{ID}=-250\mu\text{A}$
$R_{\text{DS}(\text{on})}$	Static Drain-Source On-Resistance			70	$\text{m}\Omega$	$\text{VGS}=10\text{V}, \text{ID}=-20\text{A}$
$V_{\text{GS}(\text{th})}$	Gate Threshold Voltage	-1.0		-3.0	V	$\text{VDS}=\text{VGS}, \text{ID}=-250\mu\text{A}$
I_{DSS}	Drain-to-Source Leakage Current			1	μA	$\text{VDS}=-145\text{V}, \text{VGS}=0\text{V}, \text{TJ}=25^\circ\text{C}$
I_{GSS}	Gate-Body Leakage Current			± 10	μA	$\text{VGS}=\pm 20\text{V}$
V_{SD}	Body Diode Voltage			1.5	V	$\text{VGS}=0\text{V}, \text{ISD}=-40\text{A}$
T_J, T_{stg}	Operating and Storage Temperature Range	-55~+150			°C	

Mechanical Data

Die Size	3270×5220	μm^2			
Gate Pad Size	300×400*2				
Source Pad Size	No Passivation				
Scribe Line Size	60				
Wafer Diameter	200	μm			
Wafer Thickness	175-200				
Passivation Frontside	No Passivation				
Source Metallization	AL				
Drain Metallization	Ti- Ni - Ag				
Reject Ink Dot Size	0.51				
Recommended Storage Environment	Store in original container, in dessicated nitrogen, with no contamination				

* Electrical characteristics are reported for the reference packaged part (TO-252/220) and can not be guaranteed in die sales form.

Variations in customer packaging materials, dimensions and processes may affect parametric performance.